

Advanced Quantitative Electron-Probe Microanalysis

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The Big Picture for EPMA Calibration, Measurement, Quantitation, Report

- Instrumental issues for EPMA:
 - Column-spectrometer alignment
 - Detector linearity and stability (flow, sealed)
 - WDS downtime calibration
 - Spectrometer resolution, reproducibility
 - New developments: SDD EDS mapping and quantitative analysis
- EPMA Standards:
 - Proper selection of standards (sample vs. standard)
 - Internal consistency of stds in your lab vs. international environment
- Problem Systems:
 - Peak overlaps, high-order WDS interferences
 - Analytical problems, high absorption correction
 - Correction algorithms and mass absorption coefficient data sets
- Solutions:
 - Interlaboratory collaboration, education
 - Multiple KV and multiple spectrometer analysis of core std set
 - Payoff – proof of internal std comps and empirical macs

Procedures for Quantitative EPMA, WDS Emphasis Part I – Instrument Calibration and Measurement

- Electron microprobe calibration issues
 - WDS and EDS spectrometer alignment, column alignment, (stage too)
 - WDS downtime characterization
 - WDS pulse processing, gain/bias, PHA, P-10
- EPMA Standards characterization and accuracy of analysis
 - Internal consistency of standard compositions and measurements
- WDS wavelength scans and background measurement locations
 - Full peak width, scans on stds and samples
 - Note: Valley between $K\alpha-K\beta$, $L\alpha-L\beta$, $M\alpha-M\beta$ is not true background!
- Identification of peak and background interferences
- Analytical conditions, beam sensitive materials
- New instrument, 25 year old std block with oxidized surface, why ???
- Avoid blunders
 - Reliance on software defaults, automated procedures and unattended ops
 - Setup without WDS scans, ignorance of pulse processing
 - Precision vs. accuracy issues

Calibration Issues for Electron-Probe Microanalysis

- Microprobe performance specifications are:
 - Driven by capabilities and address problem solving for customers
 - Capabilities are funded by purchases, user/vendor development
 - Realistic specifications for WDS vs. EDS systems
- Instrument calibration during installation and testing
 - Spectrometer alignment – to electron column and mutual agreement
 - Detector linearity with count rate and deadtime issues
 - Precision = reproducibility (mechanical, electronic)
 - Accuracy = correct K-ratio measured
- Instrument calibration – short vs. long term
 - Consistent performance with time
 - Accuracy in international interlaboratory environment
- Geological EPMA
 - CMAS silicate standards used for acceptance testing (CIT, WU)

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Software Tools for the Microprobe Analyst

- Interaction with experienced scientists and technicians, and thinking.
- CalcZaf – correction algorithms, mac sets, parameters
 - Generated a-factors for compact correction algorithm, testing
- DTSA II, Casino, GMRfilm, (Penelope) – scattering volume, spatial sampling, simulation of x-ray spectra
- Startwin (PFE) – bias/gain scans, pha characterization, spectrometer alignment, spectrometer reproducibility, beam stability, etc.
- Probe for EPMA – all quantitative EPMA
 - Sample setups and subsets of master element list, customized
 - Formula calculation, specified elements, etc.
 - Multiple standards comparison, standards evaluation
 - Beam sensitive materials analysis via TDI
 - Multiple spectrometer measurement of (trace) elements
 - QC with record-keeping of all peaking, PHA scans
- ProbeImage – x-ray and quantitative compositional mapping

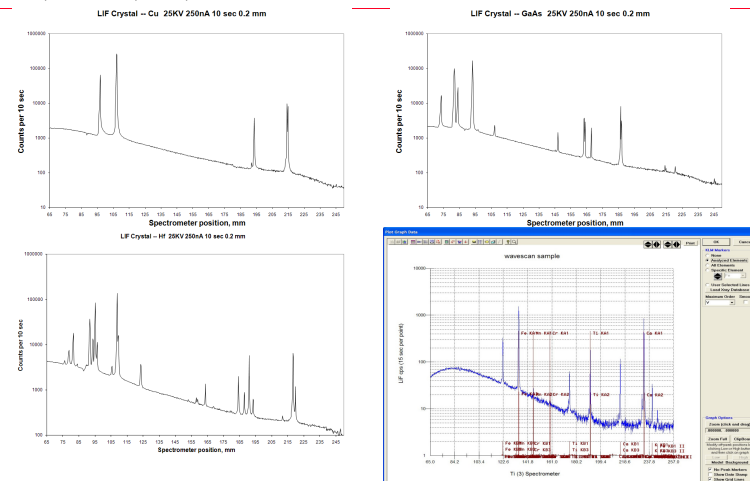
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Wavelength Scans and Interferences

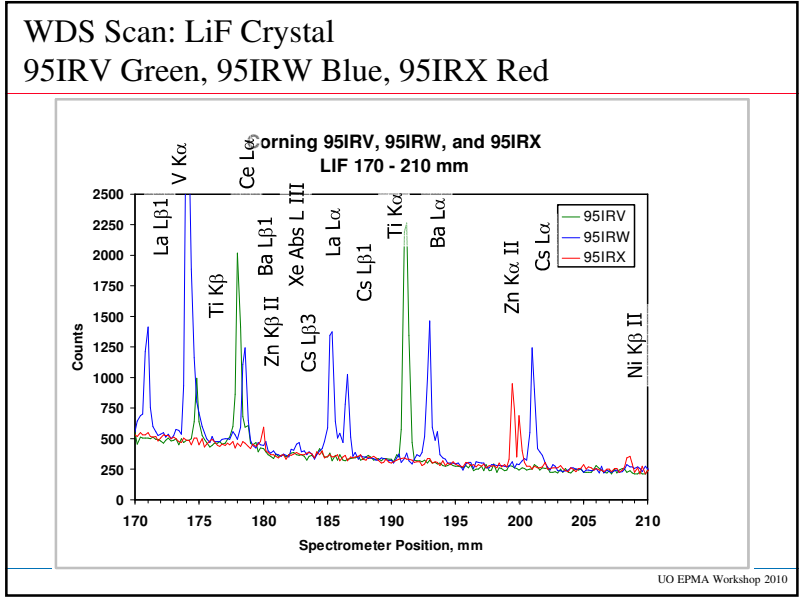
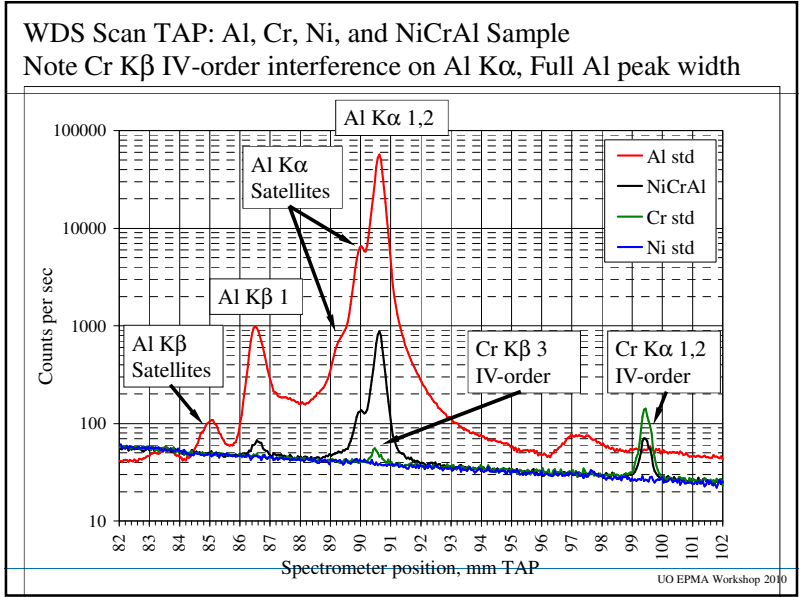
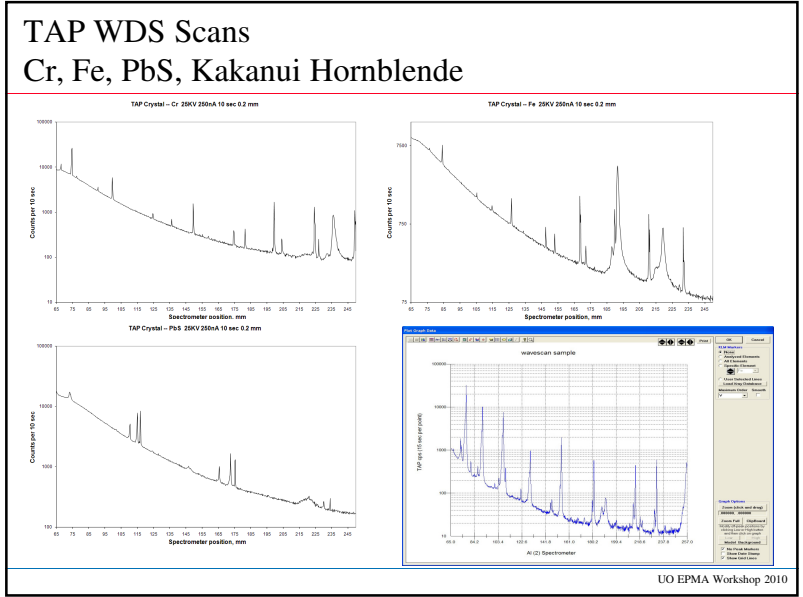
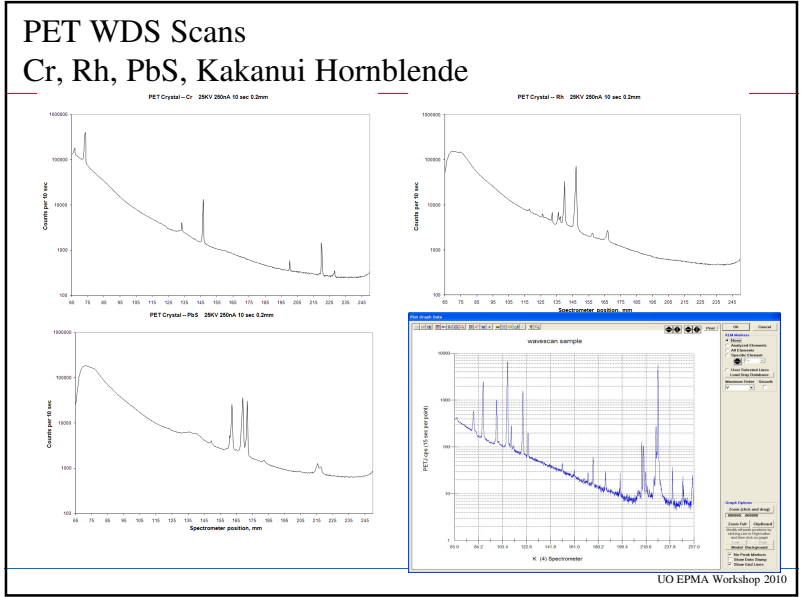
- High order interferences increase going to lower energy WDS crystals
- LiF—few, PET—more, TAP—many, LDE—up to II-order only
- Use wavescans on pure element, working standards, typical samples
- Collect scan using high kV to excite and see maximum overlaps
- Hard to visualize complex overlaps
- REE-rich phases, PGE minerals

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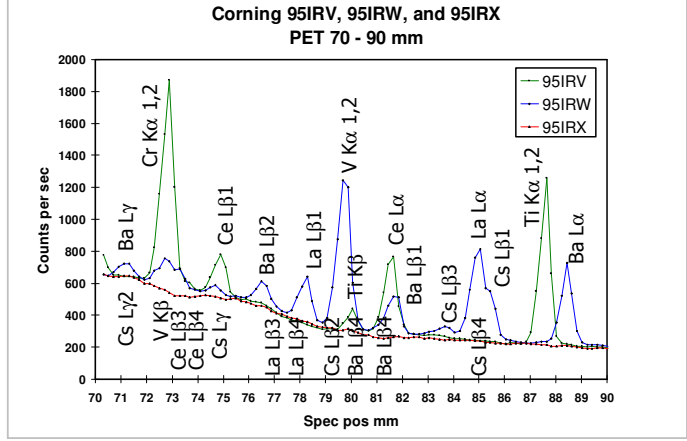
LiF WDS Scans Cu, GaAs, Hf, Kakanui Hornblende



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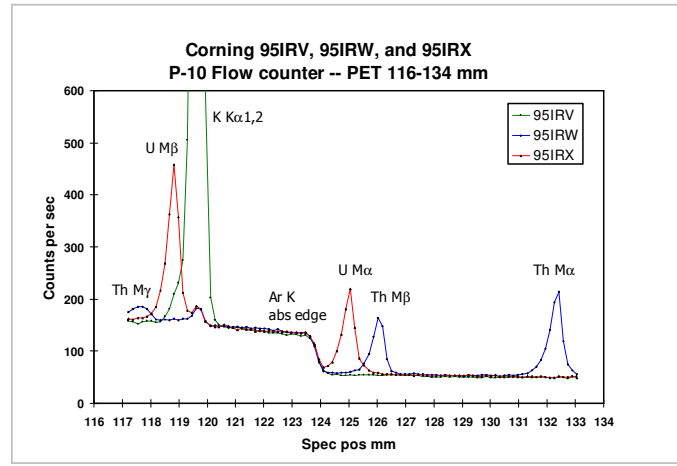


WDS Scan: PET Crystal
95IRV Green, 95IRW Blue, 95 IRX Red



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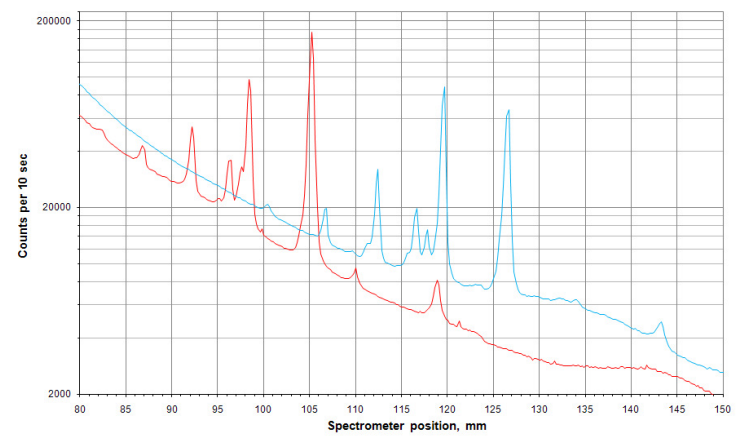
WDS Scan: PET Crystal
Th Mβ on U Mα, K Kα Peaks & Ovlp U Mβ



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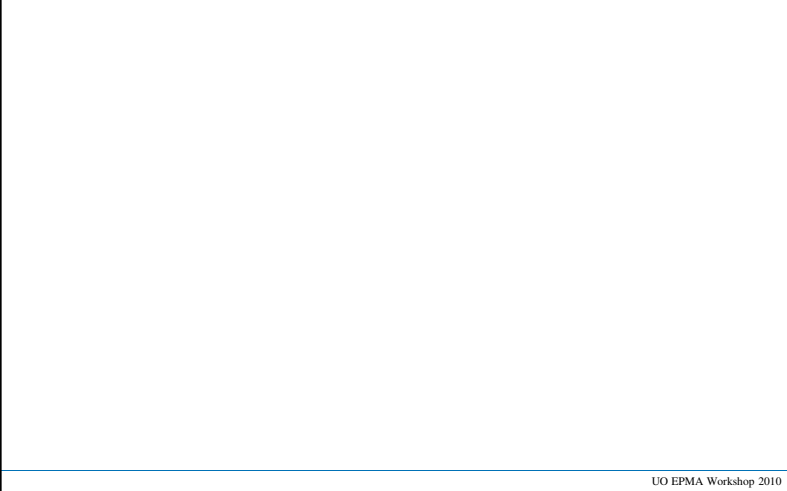
WDS Background Selection: Cd (red) Te (blue)

PET Crystal -- Cd and Te 25KV 250nA 10 sec 0.2mm



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Pulse-Height Analysis
Wavelength-dispersive spectrometer



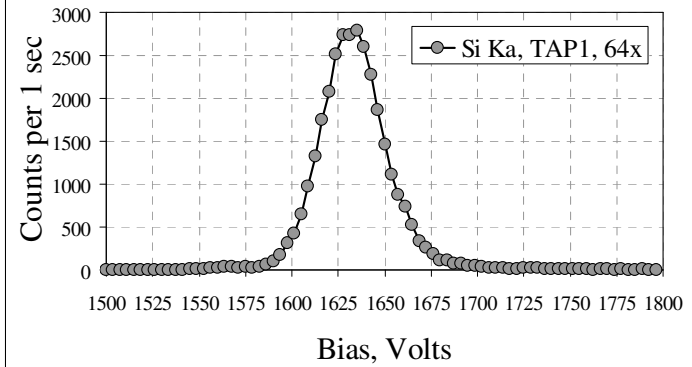
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WDS PHA Measurement

- Low energy pulses must be discriminated from baseline noise. Need proper setting of noise threshold, baseline, and window settings of WDS pulse height analyzer.
- The pulse processing circuitry of WDS does not need to deal with pulse shaping like that of EDS, and is inherently faster.
- Pulse energy shift with varying count rate results in instability. At high count rates pulses are poorly discriminated from baseline noise. Use similar count rates on standard and sample.
- Avoid tight PHA window, use integral mode unless a PHA interference is observed.
- The P-10 detector gas flow rate must be stable or else gas amplification factor varies, and so does count rate.
- Temperature variation will affect gas amplification factor as well as thermal expansion of analyzer crystal.
- Low energy peaks need to be integrated due to peak centroid and peak shape/area factors. Use area-peak factor or perform integration.

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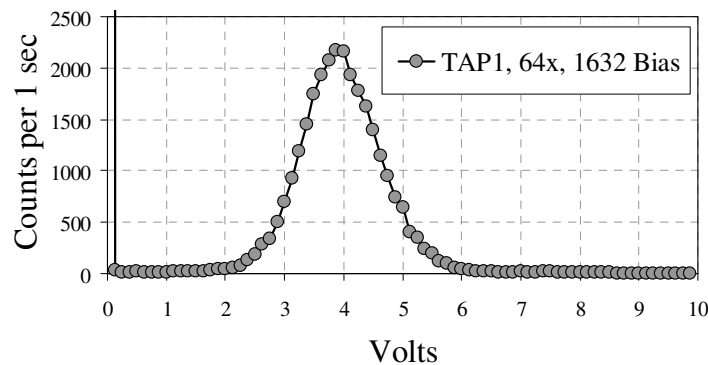
Detector Bias Scan Si K α Vary Bias at PHA Narrow Window



Detector bias scan using 3.9 volt baseline and 0.2 volt window on PHA. Intended to minimize energy gain shift of PHA.

MSFC Spec 1, P-10 flow counter, TAP, 64x gain, Si K α on SiO₂ metal @ 10k cps.

Detector PHA Scan Si K α



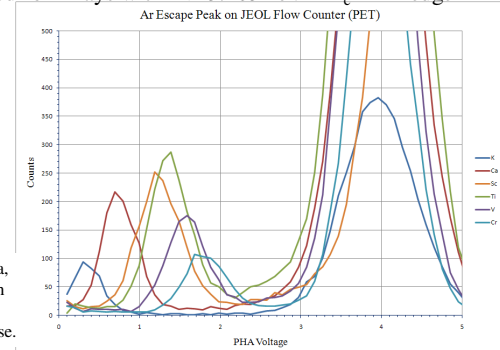
For Si K α there is good separation between baseline and Si pulses. Nominal baseline is 0.5 V with 9.5 V window (integral mode)

MSFC Spec 1, P-10 flow counter, TAP, 64x gain, Si K α on SiO₂ @ 10k cps.

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PHA Scans JEOL P-10 flow detector, PET crystal

Ar escape peak observed for x-rays with $E > 3.203 \text{ keV} = E_c \text{ Ar K-edge}$



PHA scans for K-lines of K, Ca, Sc, Ti, V, and Cr, using 64x gain and detector bias necessary to produce a 4 volt PHA x-ray pulse.

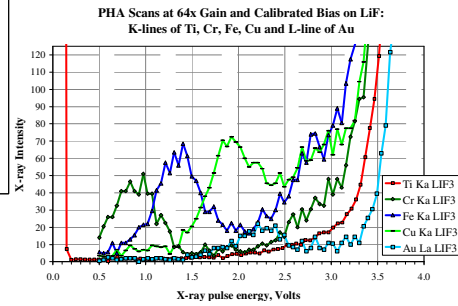
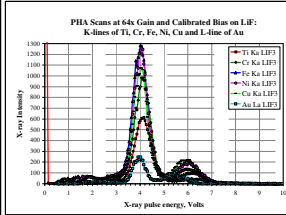
Expanded scale illustrating Ar K α escape peak position as a function of x-ray energy. As the x-ray energy increases, the Ar escape peak increases in voltage. The position of the escape peak must be treated consistently when setting the baseline of the PHA: either always include the escape peak or always exclude it, for both sample and standard measurement.

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PHA Scans

JEOL sealed Xe detector, LiF crystal

Xe escape peak observed for x-rays with $E > 5.452 \text{ keV} = E_c \text{ Xe L-edge}$



PHA scans for K-lines of Ti, Cr, Fe, Ni, and Cu, and L-line of Au, using 64x gain and detector bias necessary to produce a 4 volt PHA x-ray pulse.

Expanded scale illustrating Xe $L\alpha$ escape peak position as a function of x-ray energy. As the x-ray energy increases, the Xe escape peak increases in voltage. For Ti the escape peak is buried in the baseline noise, and for more energetic x-rays the positions are: Cr $\sim 0.9\text{V}$, Fe $\sim 1.4\text{V}$, Cu $\sim 1.9\text{V}$, and Au $\sim 2.2\text{V}$. The position of the escape peak must be treated consistently when setting the baseline of the PHA: either always include the escape peak or always exclude it, for both sample and standard measurement.

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Calibration of PHA

Using Bias vs. $\ln(E)$ plots

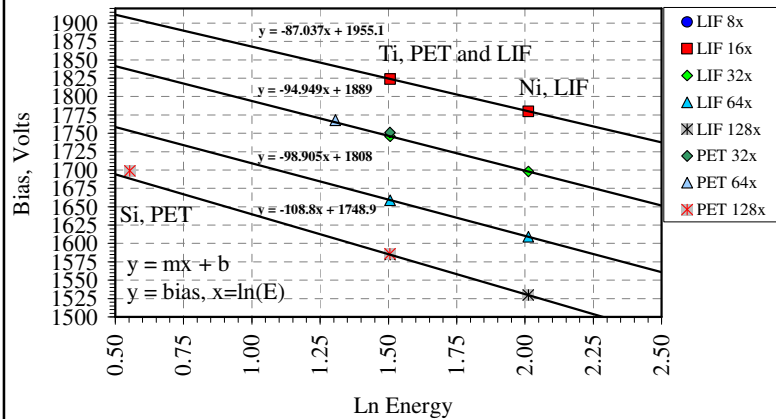
- For JEOL microprobe want SCA pulse at 4 volts, Cameca at 2 volts
- Spectrometer at peak position
- Bias scan with 3.8v base, 0.2v window gives bias for 4 volt SCA
- Plot of bias vs \ln of x-ray energy is linear
- Calibration performed for minimum element set which spans energy range of spectrometer for all analyzing crystals
- Detector should give same bias for Ti $K\alpha$ on PET vs. LIF, others
- Calibration confirms systematic behavior of x-ray counter
- As P-10 tank empties and Ar/CH_4 changes, requires recalibration
- Use $y = mx + b$ fit to bias data to provide quick calibration
- Similar plot for escape peak as function of x-ray energy

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PHA Bias Plot for LIF/PET Data

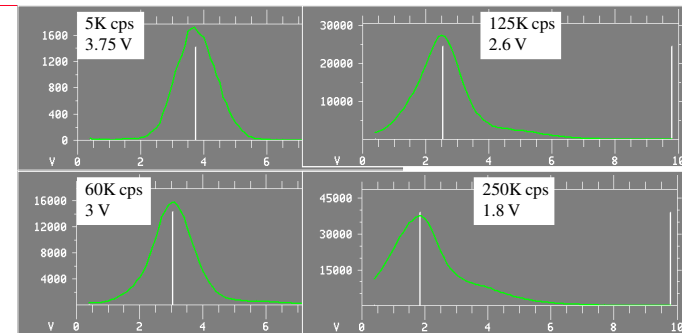
Si, Ti, Ni Bias data at 8, 16, 32, 64, and 128x Gain

WU 8200 Detector Bias Spectrometer 3
Settings for 4 Volt Pulse



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Gain Shift Due to Count Rate



Gain shift due to count rate, detector bias arbitrarily set to 1700 volts. Observed shift is ~ 0.008 volts per 1 K cps (1.95 volt shift over 245 K cps range). At $\sim 125\text{k}$ cps baseline noise discrimination deteriorates. Older PCS electronics exhibit complete shift into baseline noise. MSFC Spec 1, P-10 flow counter, TAP, 32x gain, Si $K\alpha$ on Si metal.

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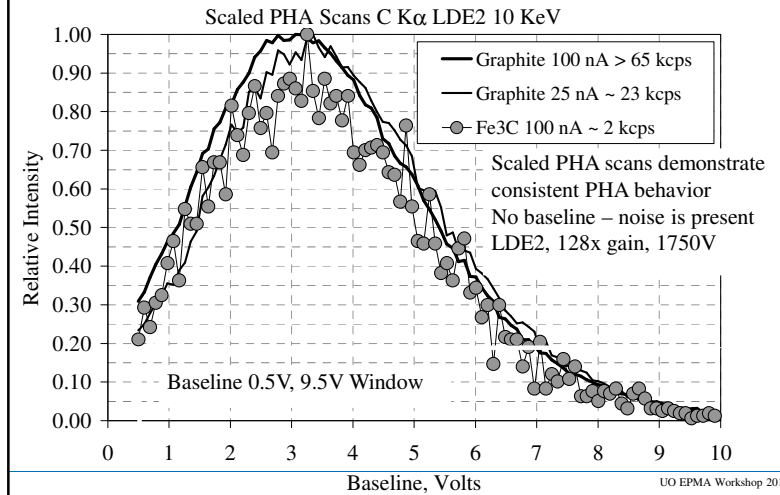
PHA Scan Ti L α 20K CPS



Light element / low energy x-rays are poorly resolved from baseline noise.
Gain shifts with count rate – PHA peak shifts toward baseline with increasing count rate. Use integral mode unless PHA energy discrimination required – counts extend to upper limit of PHA scan.
MSFC Spec 1 with P-10 flow counter, LDE2, 128x gain, Ti L α on Ti metal @ 20k cps.

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Carbon K α PHA Scans Graphite, Fe3C



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Deadtime Measurement on the Wavelength-Dispersive Spectrometer

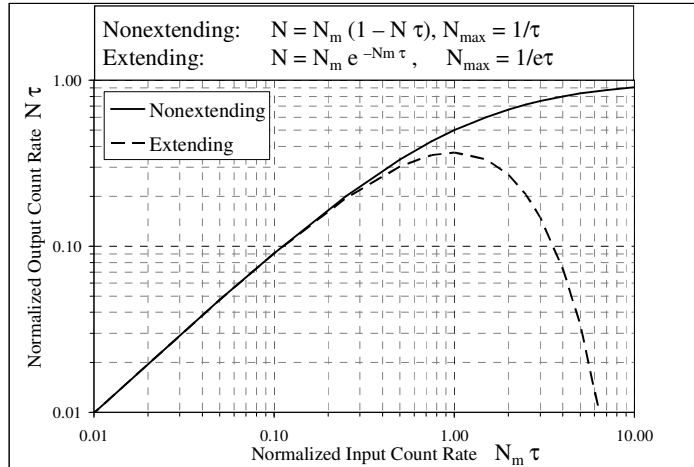
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WDS Deadtime Issues in EPMA

- Deadtime – time interval during which counting electronics are unable to process subsequent incoming pulses
- Deadtime error is non-negligible, systematic, affects all measurements
- General problem:
 - Counting behavior of WDS systems is undocumented and poorly known
 - End-users make measurements with assumed WDS deadtime behavior
 - User knowledge of deadtime issues needs improvement
- Specific problem areas:
 - No software to conveniently evaluate deadtime on turnkey systems
 - No agreed method for setting bias, gain, and sca on systems
 - SCA pulse shift behavior with count rate undocumented
 - Deadtime dependence on X-ray energy undocumented and unknown
 - Low vs. high count rate behavior and deadtimes inconsistent

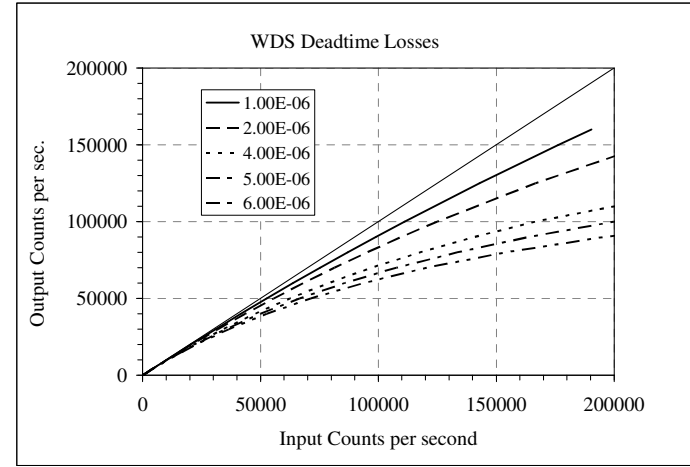
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Deadtime Behavior: Extending vs. Nonextending



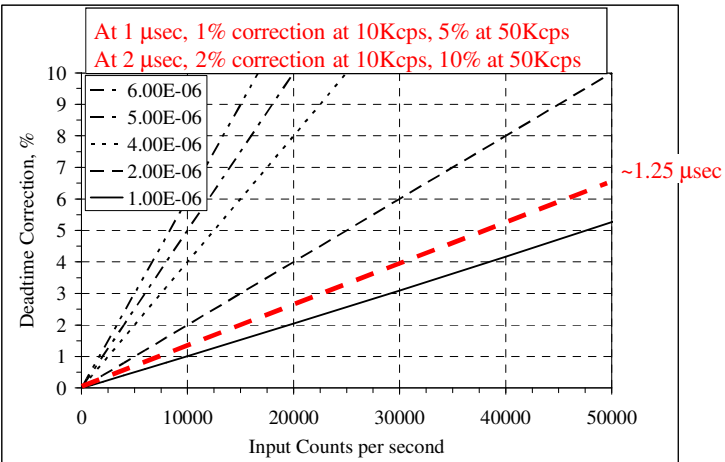
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Deadtime Losses Input – Output Curves for μ sec Deadtime Constants



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Percentage Deadtime Losses Percent Level Corrections Apply to All Measurements



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Deadtime Relations Calculation of Deadtime Constant

$$N = \frac{N_m}{(1 - N_m \tau)}$$

- N = true count rate, N_m = measured count rate with deadtime losses ($N_m < N$), and τ is the deadtime constant, which ranges from 1 to several μ sec for WDS counting systems. It is necessary to know N_m and N to calculate τ . We assume the proportionality of N to the probe current i is constant. This may not be true at low count rates.

$$\frac{N_m}{i} = c(1 - N_m \tau)$$

- N_m / i = measured count rate in counts per second per nA, and c is the constant N / i

Form: $y = mx + b$

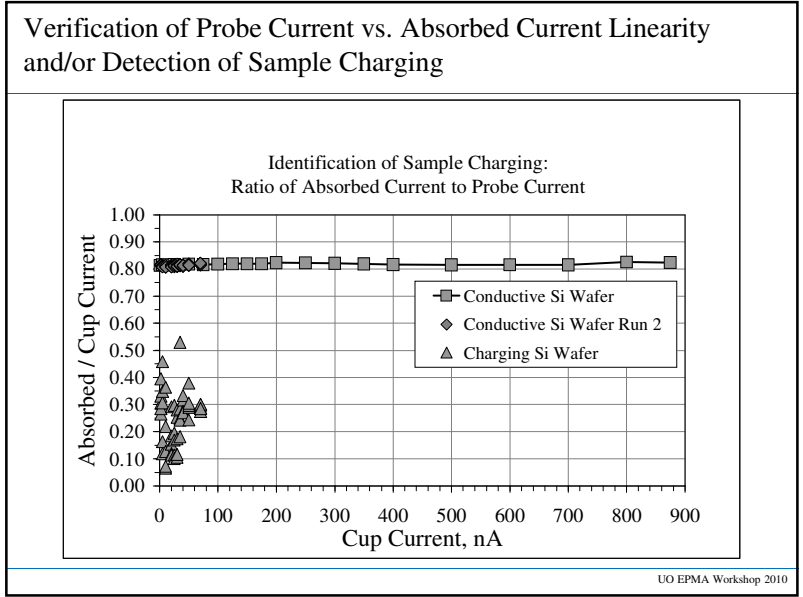
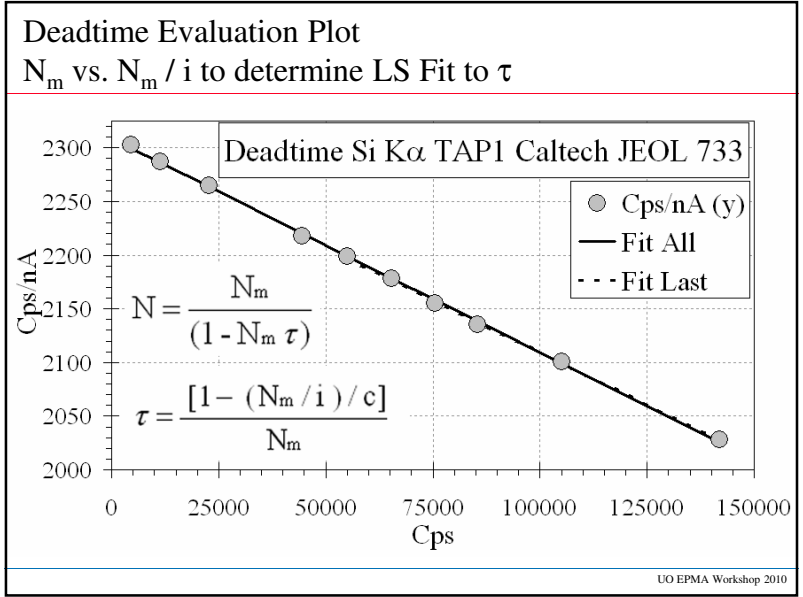
(N_m / i) is y , x is N_m , y -intercept b is constant $c (= N / i)$.

$$\tau = \frac{[1 - (N_m / i) / c]}{N_m}$$

- Equivalent to $\tau = (1 - y / b) / x$

Measure x-ray intensity at increasing probe current
Use count rate N_m and N_m / i to evaluate the deadtime constant τ over a range of intensity values

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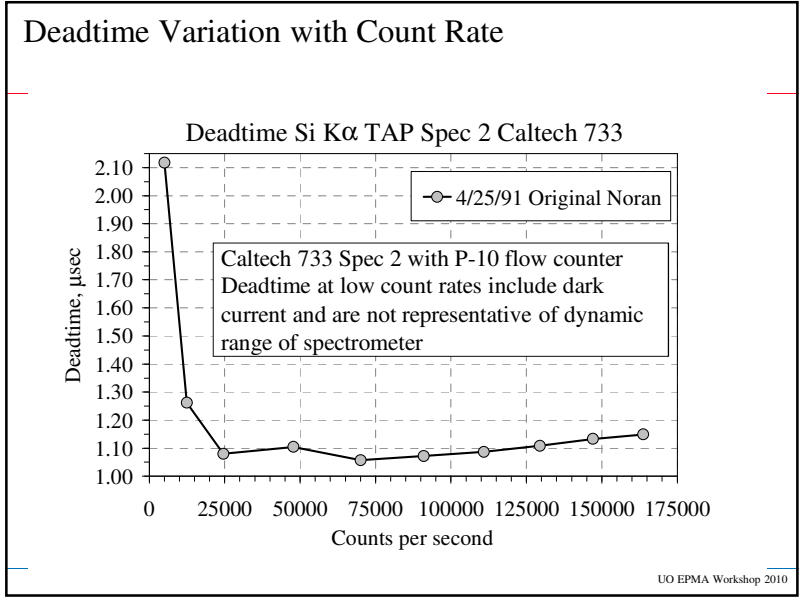


Deadtime Calculation from Excel Spreadsheet

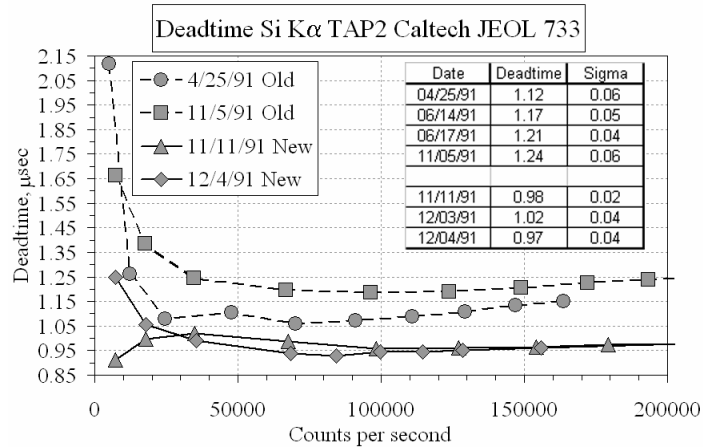
nA	Abs Cur	Abs/Probe	Time	Cps (x)	Cps/nA (y)	Fit All	Fit Last	DT us All	DT Last
2.00	1.63	0.82	100	4607.9	2302.57	2299.81		0.61	
5.00	4.05	0.81	80	11436.9	2287.20	2286.17		0.83	
10.01	8.10	0.81	80	22665.3	2264.44	2263.73		0.85	
20.05	16.25	0.81	60	44469.0	2217.95	2220.18		0.89	
25.00	20.29	0.81	60	54977.1	2199.08	2199.18	2197.08	0.87	0.83
29.98	24.34	0.81	30	65298.1	2177.91	2178.56	2177.00	0.87	0.84
35.02	28.54	0.81	30	75474.9	2155.07	2158.23	2157.20	0.88	0.86
40.05	32.53	0.81	30	85510.0	2134.97	2138.18	2137.67	0.88	0.86
49.99	40.74	0.81	30	105026.6	2101.04	2099.19	2099.70	0.86	0.84
69.98	57.25	0.82	30	141942.7	2028.45	2025.44	2027.88	0.86	0.84
Regression Output:						Mean deadtime		0.86	0.84
All	Y intercept		2309.01	Slope	-0.0020	Sigma		0.02	0.01
High CR	Y intercept		2304.04	Slope	-0.0019	Regression DT		0.87	0.84

Excel Sheet: X is N_m and Y is N_m/i . Deadtime evaluated from each intensity (DT) and from least squares fit to data (Fit) using Excel *linest* function. All data and high intensity only data are compared with average values (Mean deadtime) and standard deviation. Ratio of absorbed/probe current checks conductivity. If linear all data agree.

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Deadtime Variation With Time and P-10 Gas Chemistry Comparison of Original and New Tracor PCS Electronics



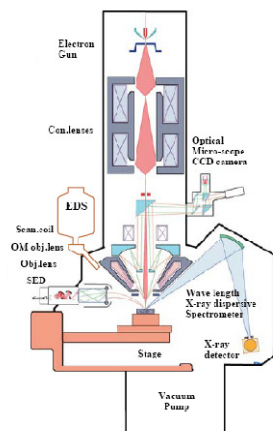
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Establishing Calibration of an Electron Microprobe

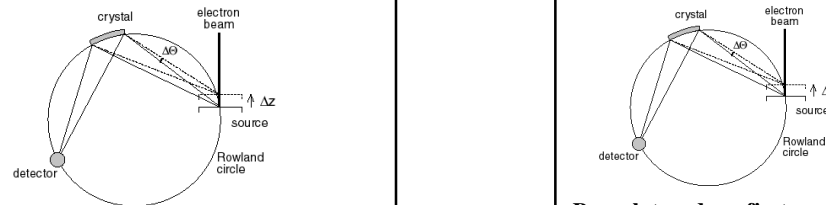
- Wavelength spectrometer aligned vertically (baseplate) to coincide with optical microscope focal point in z-space
- Diffraction crystal aligned to be on Rowland circle
- All WDS should focus on same z-axis and coincident xy area ~ 50 um in diameter
- Characteristics of correct alignment
 - All WDS & EDS have identical X-ray takeoff angle
 - Maximum X-ray intensity at z focus position, but also require: Measure identical k-ratio within counting statistics
- Simultaneous k-ratio measurement is ultimate test of alignment
- Initial CMAS standard set used on Caltech MAC and JEOL JXA-733
- Expanded CMASTF standard set used for Wash U JXA-8200

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Electron Microprobe Column Spectrometer Alignment: Baseplate and Crystal

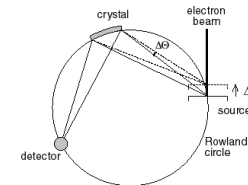


Baseplate: Place Rowland circle at Z focus
Crystal: Align all crystals on Rowland circle
 Spectrometer design keeps detector on RC
 Note: Different K-ratio = misalignment
Multiple spectrometer comparison required to demonstrate all WDS and EDS are mutually aligned



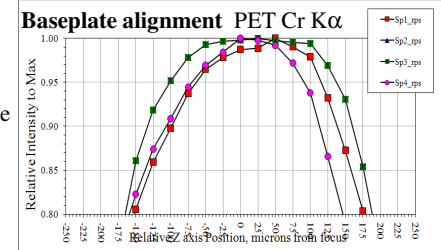
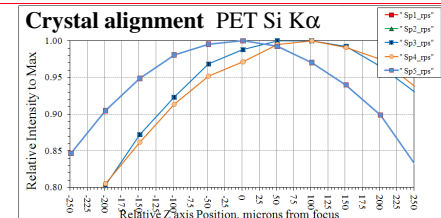
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WDS Spectrometer Alignment--Baseplate and Crystal (JEOL, vertical spectrometers)



Baseplate – done first
 Place Rowland circle at Z focus
 Use PET Cr K α , other low peak
Crystal – done for each crystal
 Align all crystals on Rowland circle
 Use PET Si K α , others

Here baseplate is set using Cr
 Crystal Spec 5 PET set, 3&4 need further adjustment



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CMASTF Silicate Standards

Geological materials are multicomponent

- End-member stoichiometric silicate and oxide mineral standards
- Primary standards:
 - MgO, Al₂O₃, SiO₂, CaSiO₃ (CaO 48.27, SiO₂ 51.73), TiO₂, and Fe₂O₃
- Analyzed suite of stoichiometric standards, natural and synthetic materials:
 - Second set of primary standards on different mounts
 - Spinel MgAl₂O₄, Enstatite MgSiO₃, Forsterite Mg₂SiO₄
 - Kyanite Al₂SiO₅
 - Fayalite Fe₂SiO₄
- Well characterized natural mineral standards and glasses:
 - Olivines (Mg,Fe)₂SiO₄
 - Diopside CaMgSi₂O₆, Anorthite CaAl₂Si₂O₈, Sphene CaTiSiO₅
 - Ilmenite FeTiO₃
 - Synthetic glasses in CMAS and CMASF system:
 - Weill CMAS glasses, NBS K411, K412

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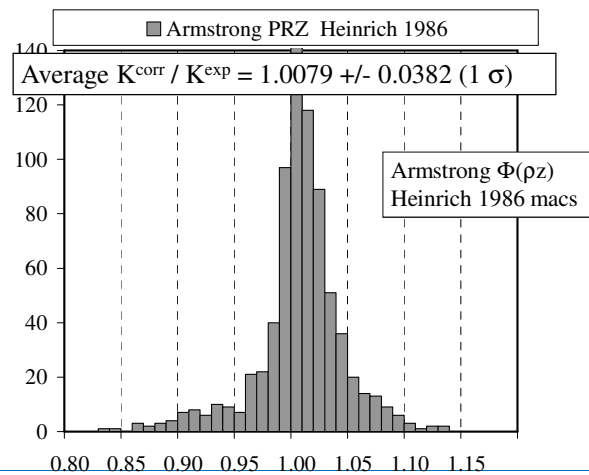
CMASTF Standard Inventory: Natural & Synthetic Composition in Wt% Oxide

Standard	MgO	Al ₂ O ₃	SiO ₂	CaO	TiO ₂	FeO* or Fe ₂ O ₃
Alaska Anorthite		36.03	44.00	19.09		0.62
Boyd Olivine	51.63		40.85			7.17
Ilmen Mtns Ilmenite	0.31				45.70	46.54
K411 Glass	14.67	0.10	54.30	15.47		14.42
K412 Glass	19.33	9.27	45.35	15.25		9.96
Kyanite P236		62.91	37.09			
Natural Bridge Diopside	18.31	0.06	55.40	25.78	0.01	0.26
ORNL, RDS Fayalite			29.49			70.51
San Carlos Olivine	49.42		40.81			9.55
Shankland Forsterite	57.30		42.70			
Springwater Olivine	43.58		38.95			16.62
Taylor Kyanite	0.00	62.70	37.00			0.16
Taylor Olivine	50.78		41.15			7.62
Taylor Sphene		1.36	30.83	28.82	37.80	0.66
Taylor Spinel	28.34	71.66				
Weill A	11.05	16.07	49.72	23.15		
Weill B	13.99	16.05	48.99	20.97		
Weill D	17.97	20.96	45.07	16.00		
Weill E*	6.00	8.99	79.97	5.04		
Weill Enstatite Glass	40.15	0.00	59.85			
Weill F	10.07	30.93	52.06	6.94		
Weill G	32.69	3.31	61.12	2.89		
Weill H	5.22	41.90	30.91	21.97		
Weill I	19.03	2.01	52.95	26.01		
Weill J	1.01	19.02	42.98	36.99		

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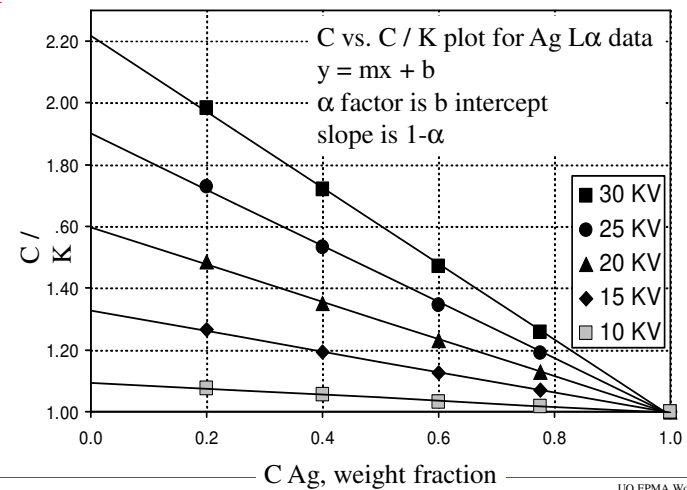
Pouchou Experimental Binary K-ratio Data Set (n=756)

Φ(ρz) Algorithm – No silicates or multi-element materials



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Ag Lα NIST SRM 481 AgAu Alloy (ψ=40)



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Accuracy Study for EPMA

Comparison of Measured to Calculated K-ratio

K_{measured} dependent on:

- Accelerating Potential
- Probe current
- Detector (gas, sealed)
- Pulse processing
- PHA calibration
- Deadtime
- Spectrometer alignment
- Sample homogeneity
- P-B determination, stripping, counting statistics
- Other sampling/drift factors

$$K_{\text{measured}} = \frac{(P - B)_{\text{sample}}}{(P - B)_{\text{standard}}}$$

$$C = K * ZAF$$

$$K_{\text{calculated}} = C / ZAF$$

K_{calculated} dependent on:

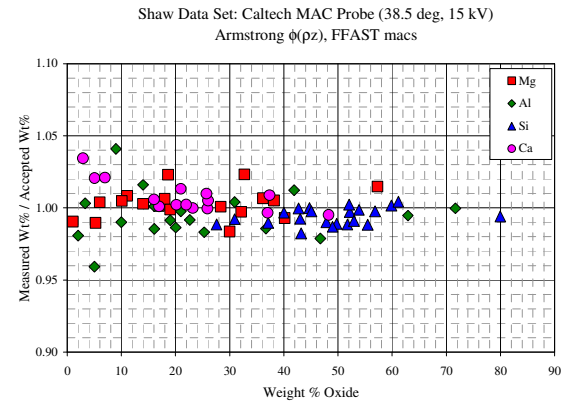
- Correct composition of standard
- Correction algorithms
- Data sets, mass absorption coefficients
- Other algorithmic factors

Evaluate : $\frac{K_{\text{measured}}}{K_{\text{calculated}}}$

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Historical CMAS Data

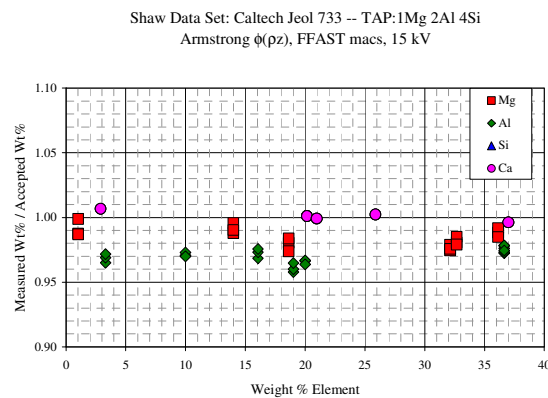
Caltech MAC Probe, Circa 1980's



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Caltech JEOL 733 1990's

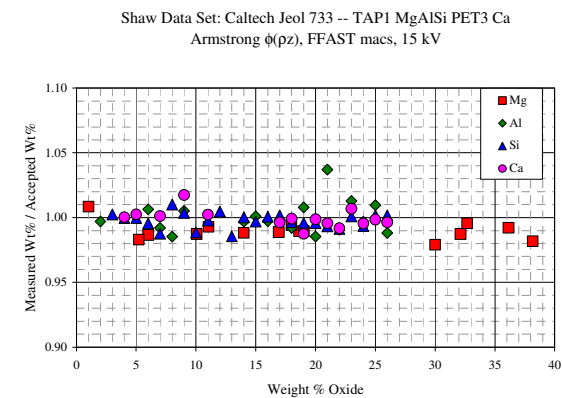
Spectrometer 124 TAP for Mg Al Si (Ca PET)



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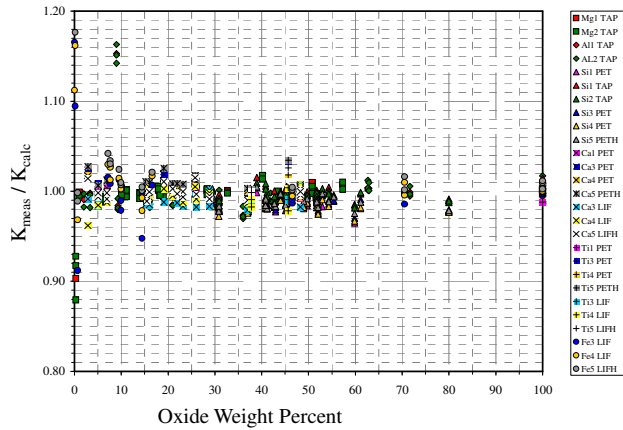
Caltech JEOL 733 1990's

Spectrometer 1 TAP for Mg Al Si (Ca PET)



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WU JXA-8200 CMASTF Data Set
All WDS Data Superimposed



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Average $K_{\text{meas}} / K_{\text{calc}}$ for CMASTF Standards
Washington University JEOL 8200

WDS	Spec 1	Spec 2	Spec 3	Spec 4	Spec 5
Mg TAP	0.9997	0.9971			
Al TAP	0.9950	0.9946			
Si TAP	0.9981	0.9955			
Si PET	0.9855		0.9865	0.9837	0.9880
Ca PET	1.0013		1.0064	1.0035	1.0101
Ca LIF			0.9908	0.9948	0.9989
Ti PET	1.0000		1.0059	1.0044	1.0115
Ti LIF			0.9919	0.9949	1.0084
Fe LIF			0.9962	1.0051	1.0131

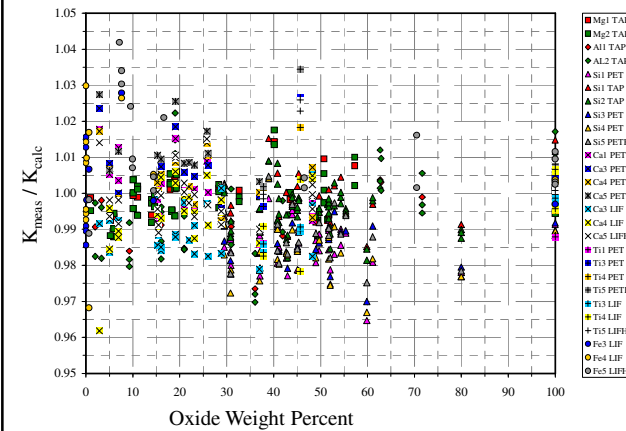
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Accuracy, 1σ % Error in $K_{\text{meas}} / K_{\text{calc}}$ CMASTF
Standards Washington University JEOL 8200

WDS	Spec 1	Spec 2	Spec 3	Spec 4	Spec 5
Mg TAP	0.65	1.30			
Al TAP	1.06	1.22			
Si TAP	0.74	0.64			
Si PET	0.71		0.71	0.75	0.70
Ca PET	0.79		0.73	0.70	0.74
Ca LIF			0.74	0.92	0.69
Ti PET	2.27		1.44	0.98	1.54
Ti LIF			0.61	1.15	1.14
Fe LIF			1.75	1.27	1.26

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WU JXA-8200 CMASTF Data Set
All WDS Data Superimposed Expanded Scale



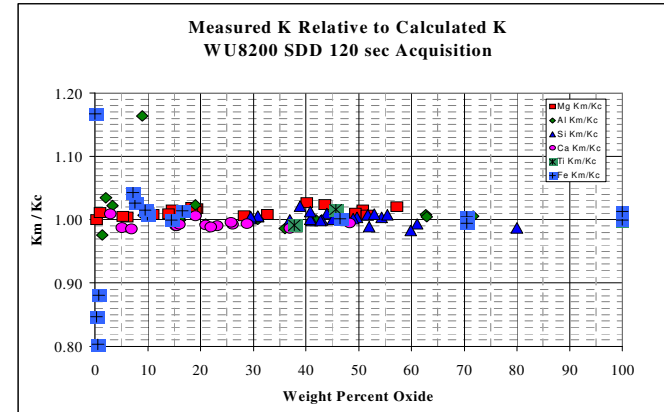
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Washington University JEOL JXA-8200 SDD Quantitative Analysis Data

- SDD great for mapping, what about quantitative analysis?
- SDD EDS data acquired at 120s, 60s, and 3s acquisitions at T3
- Standards used: MgO, Al₂O₃, SiO₂, CaSiO₃ (CaO 48.27, SiO₂ 51.73), TiO₂, and Fe₂O₃
- Linear least-squares peak deconvolution (JEOL software)
- Extracted raw K-ratios processed using Armstrong $\Phi(\rho z)$ and FFAST macros for comparison with WDS data

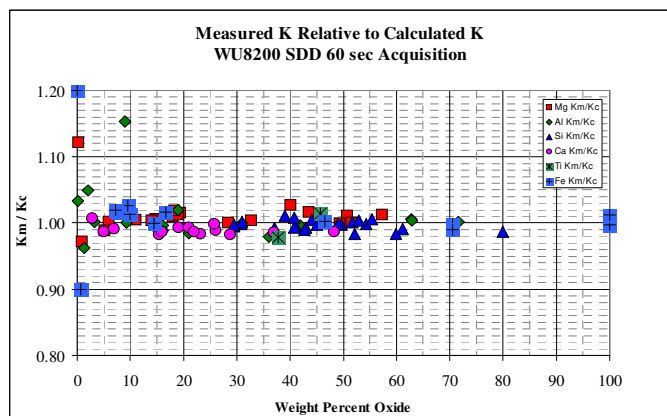
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CMASTF Standard Analyses WU8200 SDD LLSQ 120 sec. Acquisition T3



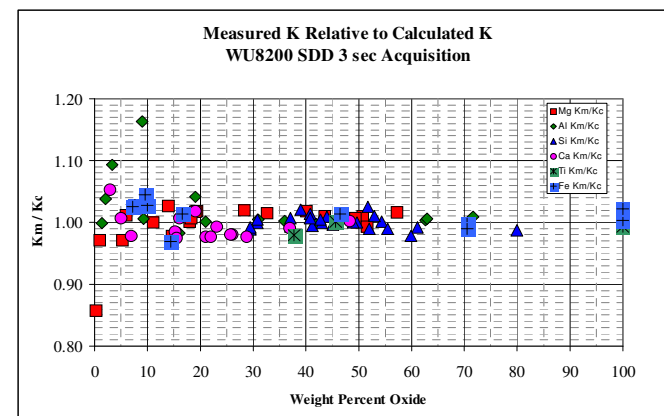
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CMASTF Standard Analyses WU8200 SDD LLSQ 60 sec. Acquisition T3



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CMASTF Standard Analyses WU8200 SDD LLSQ 3 sec. Acquisition T3



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Average Kmeas / Kcalc for CMASTF Standards
WU8200 SDD Data @ 120, 60, 3 sec acquisition T3

120s Data	Mg	Al	Si	Ca	Ti	Fe
Average	1.0122	1.0064	1.0017	0.9926	1.0021	1.0108
1 σ	0.0063	0.0122	0.0078	0.0066	0.0106	0.0140
Relative %	0.62	1.21	0.78	0.67	1.06	1.38
60s Data						
Average	1.0058	1.0022	0.9969	0.9895	0.9975	1.0083
1 σ	0.0118	0.0162	0.0069	0.0066	0.0150	0.0113
Relative %	1.17	1.61	0.69	0.67	1.51	1.12
3s Data						
Average	1.0061	1.0135	1.0001	0.9933	0.9947	1.0123
1 σ	0.0162	0.0263	0.0104	0.0213	0.0118	0.0211
Relative %	1.61	2.59	1.04	2.14	1.19	2.09

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Procedures for Quantitative EPMA, WDS Emphasis
Part II – Quantitation, X-ray Physics

- Evaluate and understand analysis for chosen system
ZAF factors for standards and samples
Identification of high x-ray absorption (kV), dissimilar std vs. sample
Attention to mass absorption coefficients
- Classify relative to representative systems, i.e.,
Absorption – Al in Mg silicates, light elements, abs edge proximity
Fluorescence, characteristic – FeNi system, secondary fluorescence
Continuum – hard line generated in light matrix, Ge Ka in GeO2
Atomic number – dissimilar Z, CuAu, SiIr, etc.

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EPMA of San Carlos Olivine
Correction Method and macs @ 20 KV, 40 TOA

Oxide	Wet Chem	PDR Ox / H66	PAPF-1 Ox / H86	Arm-1 Ox / H86	PAPF-2 Ol / H86	Arm-2 Ol / H86	PAPF-3 Ol / FF	Arm-3 Ol / FF
MgO	49.42	50.10	50.04	49.82	49.44	49.44	48.98	49.00
SiO ₂	40.81	40.74	40.66	40.07	40.56	40.58	40.34	40.69
FeO*	9.55	10.13	10.08	9.89	9.89	9.89	9.89	9.74
Total	100.29	101.66	101.47	100.47	100.60	100.60	99.90	100.12
ΣM^{2+}	2.005	2.025	2.025	2.034	2.016	2.016	2.014	2.003
Si	0.997	0.986	0.986	0.982	0.991	0.991	0.992	0.997
Mg/(Mg+Fe)	0.902	0.898	0.899	0.900	0.899	0.901	0.898	0.900

PDR: Philibert-Duncumb-Reed ZAF, oxide standards, Heinrich 1966 macs
PAPF-1 and Arm-1: $\Phi(\rho z)$ algorithms, oxide standards, Heinrich 1986 macs
PAPF-2 and Arm-2: synthetic olivine standards, Heinrich 1986 macs
PAPF-3 and Arm-3: synthetic olivine standards, FFAST macs
Same k-ratios, n=4, CaO 0.09, Cr₂O₃ 0.06, MnO 0.14, NiO 0.37 (wt %)
Olivine Formula: M²⁺₂SiO₄

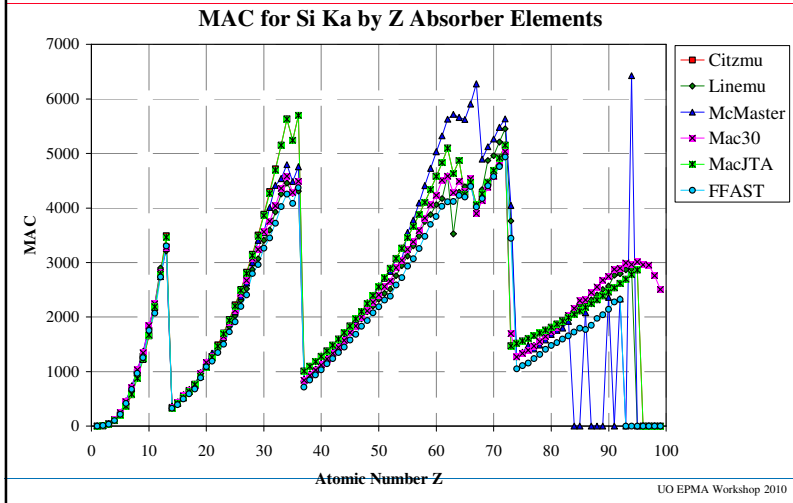
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Mass Absorption Coefficients
Example TaSi alloy

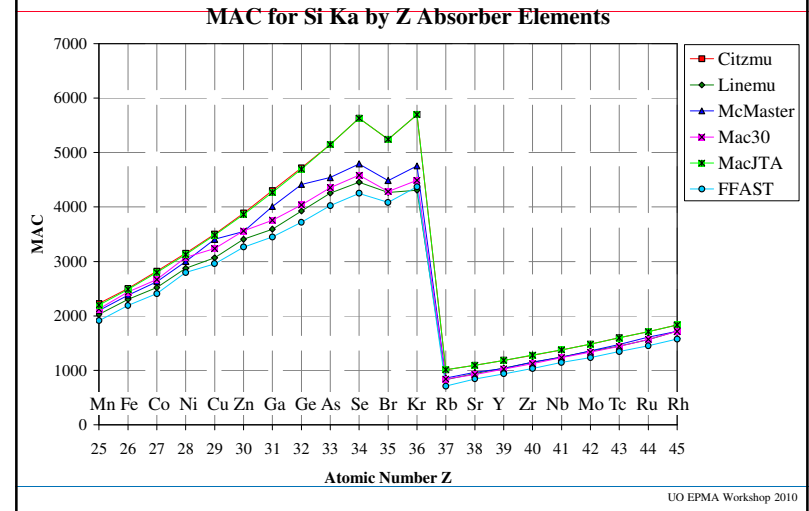
(This table area is currently blank in the provided image.)

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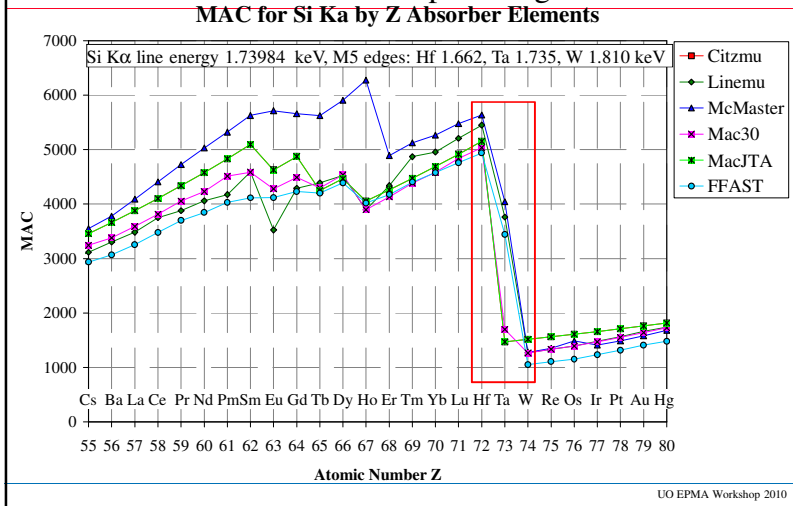
Mass Absorption Coefficients for Si $K\alpha$ By Absorber Z, All MAC Data Sets Compared



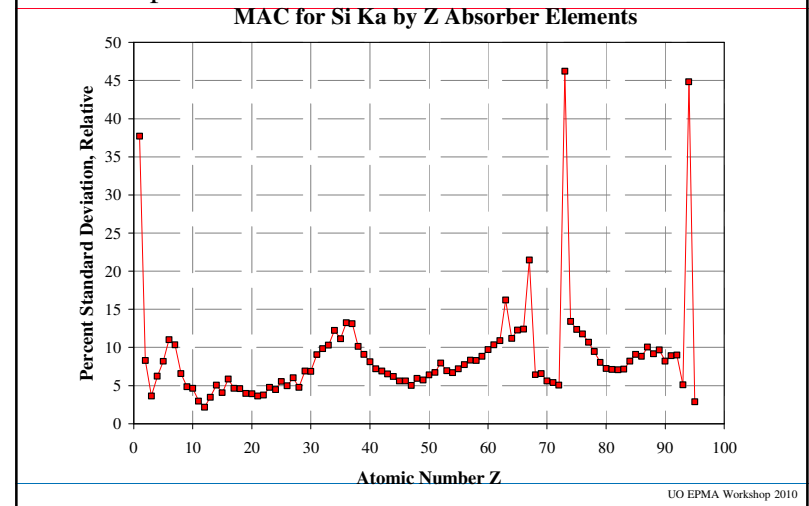
Silicon $K\alpha$ MAC at L-edge of Absorber



Silicon $K\alpha$ MAC at M-edge of Absorber Si Ka close to the Ta M5 absorption edge



Comparison of Si $K\alpha$ MACS Relative percent σ



EPMA Standards

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The Good, the Bad and the Ugly

- ***The Good, the Bad and the Ugly***
(Italian: *Il buono, il brutto, il cattivo*)
1966 Italian spaghetti western directed by Sergio Leone
Clint Eastwood as Blondie, the Good (confident bounty hunter)
Lee Van Cleef as Angel Eyes, the Bad (ruthless sociopathic killer)
Eli Wallach as Tuco, the Ugly (oafish bandit and liar)
- Third film in the Dollars trilogy
A Fistful of Dollars (1964), *For a Few Dollars More* (1965)
- Plot: three gunslingers compete to find a fortune in buried Confederate gold amid the violent chaos of gunfights, hangings, Civil War battles, and prison camps
- There are (similar?) challenges of using microanalysis standards that are Good, Bad, and just plain Ugly

M&M 2008 EPMA Standards

EPMA Standards: Desirable Attributes

- EPMA standards should be well characterized
Bulk and microchemical analysis of distribution material
XRF, ICP-MS, INAA, Classical wet chemistry, etc.
Supplemental to EPMA analysis
Traceable
- Homogeneous on micron scale
Minimal variation intra-grain and grain-to-grain
Quantitative representation of homogeneity
- Stable under electron beam bombardment and non-reactive with air
- Similar in composition to samples being analyzed
- Amenable to mounting and polishing
- Relatively large grains for use (several hundred microns minimum)
- Widely available and in sufficient quantity to international community
- Inexpensive for purchase

M&M 2008 EPMA Standards

EPMA Standards: Emphasis on Mineral and Glass Multielement Standards

- Pure element metal standards
Minimal uncertainty in composition, typically assumed pure
Useful for wide range of samples, EDS calibration
Caution: Segregations at grain boundaries, oxidation
- End-member oxides, compounds, and minerals
Assumed composition
 Al_2SiO_5 , Mg_2SiO_4 , etc., need WDS scans for minor elements
Caution: $\text{Mg}(\text{OH})_2$ on MgO , SiO_2 beam damage, etc.
Stoichiometry is powerful constraint on composition
- Intermediate Composition Minerals, Glasses
Kakanui Hornblende, K-411 glass, Corning 95-series trace glasses
Minerals have stoichiometric constraint, glasses do not
Minerals may have homogeneity issues, glasses may not

M&M 2008 EPMA Standards

EPMA Standards: Il buono, the Good

- Eugene Jarosewich – Smithsonian microbeam standards:
 - Natural and synthetic minerals and glasses
 - Classical wet chemistry for primary analytical data (published values)
 - EPMA used for intra-grain and grain-to-grain variation
 - Sigma ratio: (actual sd / counting sd) data for quantitative homogeneity
 - Sigma of all grains, measure of homogeneity
 - Sigma of worst grain, indication of other material in separate?
 - Significant amount of available material
 - Widely distributed and routinely used
 - Free for the asking
- NIST Standard Reference Materials
 - Synthetic glasses (K-411, K-412, 61X-series, others)
 - CuAu and AgAu alloys
 - Certified values from extensive chemical and homogeneity analysis

M&M 2008 EPMA Standards

EPMA Standards: Il brutto, the Bad

- Multielement standards we use fit into this category, in my opinion
- Widely distributed Taylor standards uncertain pedigree
 - Presumably EPMA analyses
 - Zircon contains inclusions, undocumented homogeneity
- Many mineral standards characterized by EPMA only
 - Few analytical details (standards, kV, instrument, correction algorithm)
 - Chemistry only reported, no k-ratios
- Informally distributed material is assumed to be that of analysis
 - Madagascar orthoclase (Fe, Ba differ)
- Material contains other elements and/or inclusions
 - Boatner REE phosphates, must use portion with lowest Pb from flux
- The upside:
 - Most of these standards could be analyzed to better their characterization

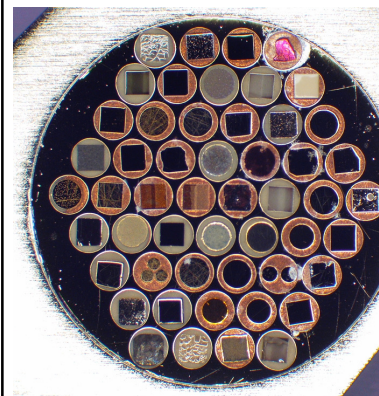
M&M 2008 EPMA Standards

EPMA Standards: Il cattivo, the Ugly

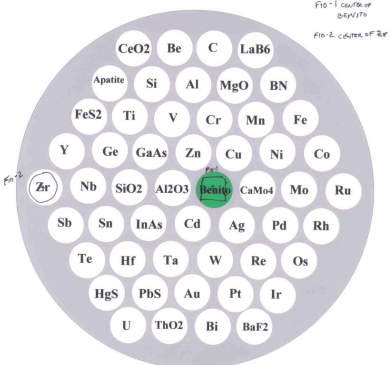
- Worst offenders are oxidized metals in commercial mounts
 - If used as sole standard serious analytical errors may result
 - Only check is total on an unknown
- Homemade mounts that have a single decrepit grain
 - Poorly polished and not even perpendicular to the beam
 - Used exclusively as the primary standard
- Mounts that have never been repolished and recoated since purchase
 - A real need exists for refurbishing services
 - ...that cost less than a new standard mount
- Again, a situation that is avoidable but is the responsibility of the analyst

M&M 2008 EPMA Standards

Taylor Commercial Mount



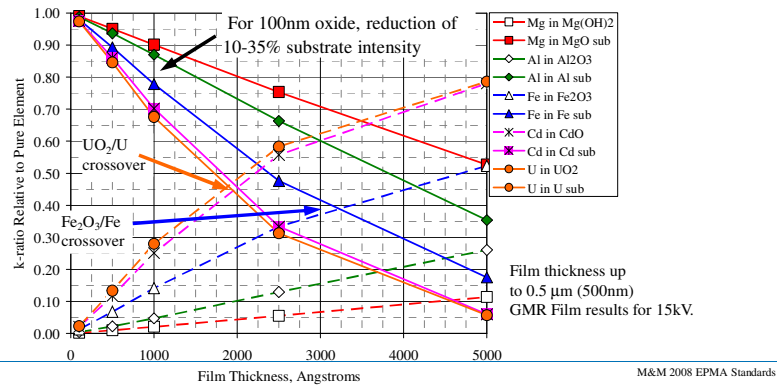
No. 203 Multi-Element Standard : T bar Left JEOL 8200
< 200 angstroms of evaporated carbon.



M&M 2008 EPMA Standards

EPMA Standards: Effect of Oxide Layer Formation Oxidized Surface = Layered Structure

Substrate reduction, oxide layer increase: k-ratio ~0.001-.003 per nm
 High Z oxides: Layer effect greater per unit thickness vs. low Z oxides
 Crossover point: $UO_2/U \sim 200nm$, $Fe_2O_3/Fe \sim 320nm$, $Al_2O_3/Al \sim 520nm$
At thickness > crossover, oxide layer dominates k-ratio measurement

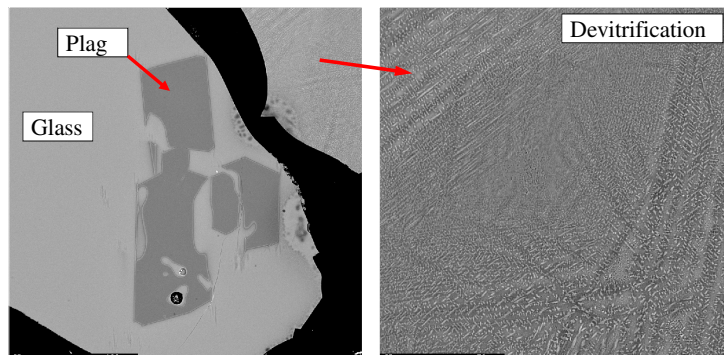


Advances in EPMA: Geological Materials -- Standards

- EPMA standards requirements: Homogeneous on micron scale, grain to grain, well characterized on both scales, and available in large enough quantity to be used by microanalysis communities.
- Most materials fail one or more of these requirements.
- Natural and synthetic minerals, oxides, and glasses. Minerals impose stoichiometry but may be inhomogeneous. Glasses lack stoichiometric control but can be homogeneous.
- Glasses: targeted compositions that can be made in bulk and utilized by the microanalysis community. (Corning 95-series trace element glasses)
- Internal consistency of EPMA standards used by the community is poorly known. Few comparison reports, generally anecdotal.
- Solution: calculate expected x-ray intensity for element of interest in suite of standards, compare measured intensities relative to end-member standard (oxide), i.e., $k = ZAF / C$. This highlights errors in composition as well as systematic errors in algorithm.

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Basalt Glass Indian Ocean USNM 113716: EPMA vs. Wet Chemistry Data



Of the 3-5 mounts of USNM 113716, this is the first observation of mineral inclusions or crystallites in the glass. This is otherwise a homogeneous standard, consistent with EPMA of other glasses, but based on wet chemistry comparison.

How representative is this of the wet chemical analysis?

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Olivine Standards: Mg-rich $(Mg,Fe)_2SiO_4$

Standard	Nat./Syn.	Minor/Trace Els.
Shankland forsterite Fo ₁₀₀	Synthetic	Fe?
Boyd olivine Fo ₉₃	Natural	Mn, Co, Ni, Zn?
LLNL "Fo85" (Fo ₉₃)	Synthetic	<none>
San Carlos olivine Fo ₉₀	Natural	Na?, Mg, Al, Ca, Ti?, Cr, Mn, Co, Ni
Fujisawa sintered Fo ₉₀	Synthetic	Al, Ca, Mn, Zn
LLNL "Fo80" (Fo ₈₅)	Synthetic	Al, Ca, Cr, Mn, Co?, Ni?
Springwater olivine Fo ₈₂	Natural	Ca, Cr, Mn
LLNL "Fo67" (Fo ₇₀)	Synthetic	<none>

Shankland from ORNL

LLNL olivines from George Rossman, Boyd and Fujisawa from Caltech

San Carlos and Springwater olivine from Smithsonian

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Olivine Standards: Mn, Fe, Ni

Standard	Nat./Syn.	Minor/Trace Els.
Mn-olivine GRR-392	Synthetic	Fe
Mn-olivine RDS P-1087	Synthetic	Mg, Ca, Fe
Fayalite GRR-391	Synthetic	Mn
Fayalite RDS P-1086	Synthetic	Mg, Cr, Mn
Rockport Fayalite	Natural	Mg, Ca, Cr, Mn, Zn
Fayalite ORNL	Synthetic	Al?, Ca?, Cr
Ni-olivine P-877	Synthetic	Cr?, Fe, Co

GRR and RDS from George Rossman, P numbers Caltech probe standards
Rockport Fayalite from Smithsonian

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Rockport Fayalite

- RF is widely used as primary Fe standard
But Mg and Zn present, not in wet chemistry analysis
[Low level oxides suspected to be variable not reported in wc analysis]
- Is ferric iron present? – apparently not:
Wet Chemistry: Fe₂O₃ 1.32, FeO 66.36 %, Tot: 99.18
Dyar XANES: RF iron is completely reduced.
- Grunerite in separate: Fe₇²⁺Si₈O₂₂(OH)₂
- Magnetite at locality, in separate (Fe₂³⁺Fe₂²⁺O₄) ??
- Analysts should use EPMA analysis when using RF as primary standard.

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Rockport Fayalite

Complete analysis needed for quantitative correction

	ELEMENT	K-VALUE	ELEMWT%	OXIDWT%	ATOMIC%	FORMULA	KILOVOL
Wet chem missing elements	Si ka	.10211	13.659	29.221	14.299	1.001	15.0
	Fe ka	.47949	52.508	67.551	27.644	1.935	15.0
	Ti ka	.00024	.024	.040	.015	.001	15.0
	Mn ka	.01487	1.657	2.140	.887	.062	15.0
	O			31.104	.000	57.156	4.000
	TOTAL:			98.952	98.952	100.000	6.998

	ELEMENT	K-VALUE	ELEMWT%	OXIDWT%	ATOMIC%	FORMULA	KILOVOL
Wet chem plus EPMA data	Si ka	.10195	13.659	29.221	14.214	.995	15.0
	Fe ka	.47983	52.508	67.551	27.480	1.924	15.0
	Ti ka	.00024	.024	.040	.015	.001	15.0
	Mn ka	.01488	1.657	2.140	.882	.062	15.0
	Mg ka	.00014	.028	.046	.033	.002	15.0
	Ca ka	.00032	.032	.045	.023	.002	15.0
	Cr ka	.00045	.040	.059	.023	.002	15.0
	Ni ka	.00005	.006	.007	.003	.000	15.0
	Zn ka	.00394	.462	.575	.207	.014	15.0
	O			31.269	.000	57.120	4.000
	TOTAL:			99.684	99.684	100.000	7.003

M&M 2008 EPMA Standards

Fayalite Standards

Oxide	Rockport Wet Chemistry	Rockport EPMA	RDS P-1086 EPMA	GRR391 EPMA**
MgO	Not reported	0.046	0.385	0
SiO ₂	29.22	29.99	30.04	(29.49)
CaO		0.045	0	0.004
Cr ₂ O ₃		0.059	0	0.010
MnO	2.14	2.13	0.092	0.212
FeO*	67.55	67.62	69.61	(70.34)
NiO		0.007	0.012	0.011
ZnO	Not reported	0.575	0.006	0.007
Total	99.18	100.48	100.16	(100.04)
Σ M ²⁺	1.999	1.982	1.979	1.999
Si	1.001	1.009	1.010	1.000

Rockport WC: FeO 66.36, Fe₂O₃ 1.32, FeO* 67.55, TiO₂ 0.04, H₂O 0.1

EPMA: PAPF, olivine stds, Heinrich 1986 macs, 20KV, n=4 **GRR391 std Si, Fe

IA Workshop 2010

Systematic Errors in Olivine $M^{2+}_2SiO_4$

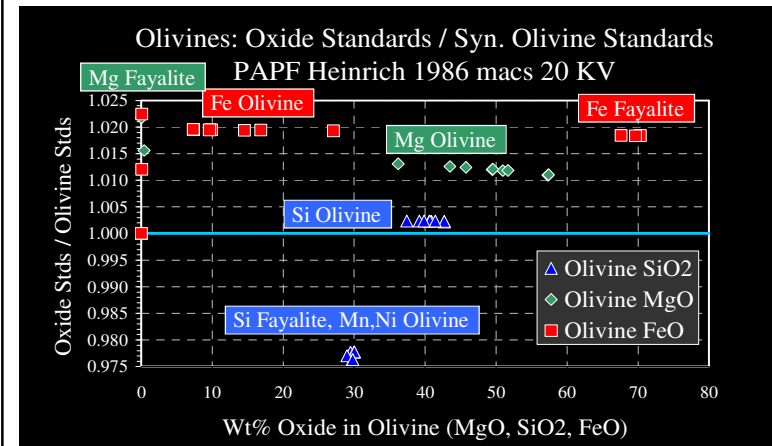
PAPF, Heinrich 1986 macs @ 20 KV, 40 TOA

Olivine Group	Standard Type	Analysis Total	σ , wt%	Si cations 1 ideal	σ	ΣM^{2+} 2 ideal	σ
Olivines	Oxide	101.14	0.42	0.989	0.004	2.023	0.007
	Syn. Olivine	100.22	0.37	0.994	0.003	2.012	0.006
Fayalites	Oxide	100.93	0.20	0.990	0.001	2.022	0.001
	Syn. Olivine	100.34	0.23	1.010	0.001	1.981	0.003
Mn,Ni Olivines	Oxide	99.32	0.33	0.991	0.003	2.018	0.006
	Syn. Olivine	100.07	0.30	1.002	0.003	1.995	0.005

Averages of total and cation stoichiometry for all olivines from test data set.
 For olivines, $Mg/(Mg+Fe) = 0.860 \pm 0.080$ (ox) vs. 0.861 ± 0.079 (oliv).
 Identical k-ratios corrected using PAP full $\Phi(\rho z)$ and Heinrich 1986 macs, relative to oxide vs. synthetic olivine standards.
 Olivine Formula: $M^{2+}_2SiO_4$

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Systematic Error Using Oxide Standards



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Status Report: EPMA of Olivine

- EPMA using synthetic olivine standards better than oxide standards:
 Superior analysis total, Si cation ~ 1.0 , and $\Sigma M^{2+} \sim 2.0$
- Improvement in EPMA accuracy for olivine using
 Armstrong $\Phi(\rho z)$ coupled with FFAST mac data set.
- Using oxide standards we observe:
 Overcorrection of Mg and Fe in olivine across Fo-Fa binary
 Undercorrection of Si in low-Mg olivine (Fayalite, Mn-ol, and Ni-ol)
 Marginal underestimation of $Mg/(Mg+Fe)$.
- These relationships extend to all MgFe silicates relative to composition.
- Alpha-factor analysis of systematic errors in Fo-Fa system:
 EPMA and wet chemistry of natural olivines are not internally consistent.
 Worst: Boyd Forsterite Mg and Fe not consistent (Caltech standard)
 Best: Springwater Mg,Fe, and Mg in San Carlos (Fe in SC less so)

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Conclusions

- Quantitative EPMA emphasizes
 Measurement issues and instrumental calibration
 Use of good microanalysis standards
 Attention to details of correction algorithms and data sets
- Experimental approach which confirms all is well:
 Use of K_{meas}/K_{calc} plot used for data analysis, WDS and EDS
 CMASTF standards provide instrument calibration data set
 Identification of inconsistent compositions
- Accuracy of analysis in CMASTF system better than 2%, precision limited
 SDD quantitative analysis data highly competitive with WDS
- Always think:
 Calibration, measurement, quantitation, evaluation, report and discuss

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